

Notice of References Cited	Application/Control No. 10/604,651	Applicant(s)/Patent Under Reexamination PENG ET AL.	
	Examiner Alexander G. Ghyka	Art Unit 2812	Page 1 of 1

U.S. PATENT DOCUMENTS					
*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,610,142	08-2003	Takayama et al.	117/8
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS						
*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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NON-PATENT DOCUMENTS		
*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	JEN et al, Effects of N2O Plasma treatment... , Japanese Journal of Applied Physics, Part 2, Letter 1994
	V	Luan et al, Effects of NH3 Plasma, J. Applied Physics, 68(7), October 1990
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	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.

Notice of References Cited
Alex Ghyka 4/13/05